

L Number	Hits	Search Text	DB	Time stamp
1	1514	(wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam	USPAT; US-PGPUB; DERWENT	2003/08/22 07:21
2	844	((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)	USPAT; US-PGPUB; DERWENT	2003/08/22 07:00
3	299	((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)	USPAT; US-PGPUB; DERWENT	2003/08/22 07:01
4	947	(wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam	USPAT; US-PGPUB; DERWENT	2003/08/22 07:56
5	537	((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)	USPAT; US-PGPUB; DERWENT	2003/08/22 07:57
6	238	((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)) not (((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam))	USPAT; US-PGPUB; DERWENT	2003/08/22 07:23
7	180	(wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam	EPO; JPO	2003/08/22 08:12
8	83	((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)	EPO; JPO	2003/08/22 08:11
9	171	(airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)	EPO; JPO	2003/08/22 08:12
10	4	((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)) and (electron adj beam or ultraviolet)	EPO; JPO	2003/08/22 08:13

L Number	Hits	Search Text	DB	Time stamp
1	1514	(wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam	USPAT; US-PGPUB; DERWENT	2003/08/22 07:21
2	844	((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)	USPAT; US-PGPUB; DERWENT	2003/08/22 07:00
3	299	((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)	USPAT; US-PGPUB; DERWENT	2003/08/22 07:01
4	947	(wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam	USPAT; US-PGPUB; DERWENT	2003/08/22 07:56
5	537	((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)	USPAT; US-PGPUB; DERWENT	2003/08/22 07:57
6	238	((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)) not (((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam))	USPAT; US-PGPUB; DERWENT	2003/08/22 07:23
7	180	(wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam	EPO; JPO	2003/08/22 08:19
8	83	((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)	EPO; JPO	2003/08/22 08:11
9	171	(airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)	EPO; JPO	2003/08/22 08:41
10	4	((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)) and (electron adj beam or ultraviolet)	EPO; JPO	2003/08/22 08:13
11	1268	(wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)	EPO; JPO	2003/08/22 08:44
12	349	((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)) and (wafer or substrate)	EPO; JPO	2003/08/22 08:20
13	348	((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)) and (wafer or substrate)) not ((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))	EPO; JPO	2003/08/22 08:21
14	0	(airtight or hermetic\$5) and (((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)) and (wafer or substrate)) not ((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)))	EPO; JPO	2003/08/22 08:46

15	46	(evacuat\$3 or vacuum\$3) and (((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)) and (wafer or substrate)) not ((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)))	EPO; JPO	2003/08/22 08:28
16	46	((evacuat\$3 or vacuum\$3) and (((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)) and (wafer or substrate)) not ((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)))) and (liquid or wet or solution)	EPO; JPO	2003/08/22 08:28
18	41377	(vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)	USPAT; US-PGPUB; DERWENT	2003/08/22 08:42
19	21350	(liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))	USPAT; US-PGPUB; DERWENT	2003/08/22 08:43
22	5998	((liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) and ((wash\$3 or rins\$3 or clean\$3) or (liquid or solution)) same (electron adj beam or ultraviolet or x adj ray or gamma)	USPAT; US-PGPUB; DERWENT	2003/08/22 08:46
23	0	(airtight or hermetic\$5) and (((liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) and ((wash\$3 or rins\$3 or clean\$3) or (liquid or solution)) same (electron adj beam or ultraviolet or x adj ray or gamma))	EPO; JPO	2003/08/22 08:47
26	7	((liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) and ((wash\$3 or rins\$3 or clean\$3) or (liquid or solution)) same (electron adj beam or ultraviolet or x adj ray or gamma)) and 396/611.ccls.	USPAT; US-PGPUB; DERWENT	2003/08/22 08:52
27	475	((liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) and ((wash\$3 or rins\$3 or clean\$3) or (liquid or solution)) same (electron adj beam or ultraviolet or x adj ray or gamma)) and ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)	USPAT; US-PGPUB; DERWENT	2003/08/22 08:53

28	192	(((liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) and ((wash\$3 or rins\$3 or clean\$3) or (liquid or solution)) same (electron adj beam or ultraviolet or x adj ray or gamma)) and ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)) not (((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)) or (((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)) not (((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam))) or (((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)))	USPAT; US-PGPUB; DERWENT	2003/08/22 08:53
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